

# CTP-A

## THERMAL CTP ANODIZED PLATE



**LP**  
**LITHOPLATE**  
PLATES AND PRODUCTS FOR-OFFSET

# Thermal CTP Anodized Plate

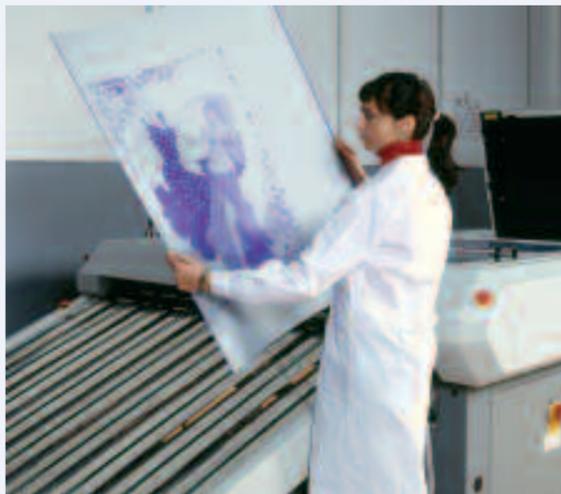
# Technical Characteristics

High performance thermal CTP plate with Electro-chemical graining, Anodizing and Hydrophilic treatment of Aluminium and improved 830 nm sensitive coating

Thermal positive plate to operate in CTP systems with infrared (IR) laser diode between 800-850 nm. No pre-heat required. Anodized non-image area.

## BENEFITS

- Easy exposure and processing
- Compatible with most of the thermal plates and developers available on the market
- Maximum resolution for the reproduction of stochastic screens
- Fast ink-water balance
- Enhanced contrast and stability
- Runs more than 100.000 impressions without baking
- Cost-effective. CTP-A plate meets user's needs and optimizes the printing performance.



## Exposure / Coating

Coating colour: blue intense  
Contrast after development: very high  
Day light sensitivity: up to 2 hours exposure does not affect the plate.  
Spectral sensitivity: 800-850 nm. Peak sensitivity at 830 nm.  
Compatible with most of the thermal platesetters: Creo, Heidelberg, Screen, Lüscher, etc...  
Required energy: 120-130 mj/cm<sup>2</sup>  
Image reproduction: 1-99 % at 250 lines per inch and FM screening

## Development

Use developer Revelith-CTP at 23°C ± 1°C  
Compatible with most of the thermal plate developers on the market  
Development time: 30 seconds ± 5 seconds  
Replenishment: with the same developer at 120-140 ml/m<sup>2</sup>

## Gumming

Use Gomalux-LP  
When hardened by baking, apply Quemagum-LP

## Deletion

Use deletion pens Dualpoint-LP

## Baking

Hardening the coating by baking enables very long runs, over 500.000 impressions, depending on press conditions.  
Apply Quemagum-LP  
Baking conditions: Static oven: 200-230°C during 5-6 minutes  
On-line oven: 230-250°C during 3-4 minutes